

## ABSTRACT OF THE DISCLOSURE

The invention relates to a pattern forming method, a method of manufacturing a TFT substrate, a method of manufacturing a liquid crystal display and an exposure mask and provides a pattern forming method, a method of manufacturing a TFT substrate, a method of manufacturing a liquid crystal display and an exposure mask which make it possible to provide a liquid crystal display having high display characteristics. In a pattern forming method for forming a resist pattern extending across a first divided exposure region and a second divided exposure region among a plurality of divided exposure regions on a substrate, a resist film is formed on the substrate; the resist film in the first divided exposure region is exposed using an exposure mask to form a latent image which defines one edge of a resist pattern in the vicinity of a boundary between the first divided exposure region and the second divided exposure region; the resist film in the second divided exposure region is exposed using another exposure mask to form a latent image which defines another edge of the resist pattern in the vicinity of the boundary; and the resist film is developed to form the resist pattern.